

*CONF C2*

(wavelength 248 nm), ArF (wavelength 193 nm), KrCl (wavelength 232 nm), and the like may be used. Also, Ar laser, YAG laser having at least one of second to the fourth [high grade] harmonic waves, etc. may be used.

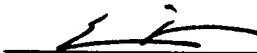
#### REMARKS

The Notice of Allowance mailed December 18, 2001 has been received and its contents carefully reviewed. The present amendment is submitted under 37 C.F.R. §1.312 in order to make corrections to the specification of the subject application due to an apparent error in translation. This error has recently come to Applicants' attention, and thus, could not be earlier corrected. Moreover, it is submitted that this amendment does not affect the allowance of this application and that this application is now in even better condition for issue. In this regard, Applicants felt that the English translation of the Japanese term for "harmonic," was not entirely accurate. Thus, the term "high grade" has been amended in order to reflect its intended meaning of "harmonic." Applicant respectfully submits that the term "harmonic" is supported in the Japanese application. Accordingly, this change in terminology does not constitute new matter. Review and approval of these amendment is respectfully requested.

If the Examiner feels that any further discussions about this case would be beneficial, he is invited to contact the undersigned.

Respectfully submitted,

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Marked-Up copy of Specification

On page 17, the fourth full paragraph, please substitute therefor the following paragraph.

--When YAG laser is used for the purpose of crystallizing a film containing silicon as a main component, a wave length having at least one of the second to the fourth [high grade] harmonic waves is used. Further, when YAG laser is used for the purpose of activating or/and laser annealing, a wave length containing one or a plurality of the basic wave to the fourth [high grade] harmonic waves is used.--

On page 23, the first full paragraph, please substitute therefor the following paragraph.

--As the laser beam generating unit 801, the unit for oscillating XeCl excimer laser (wavelength 309 nm) is used. Other than this, excimer laser such as KrF excimer laser (wavelength 248 nm), ArF (wavelength 193 nm), KrCl (wavelength 232 nm), and the like may be used. Also, Ar laser, YAG laser having at least one of second to the fourth [high grade] harmonic waves, etc. may be used.--